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Erratum

정오 "반도체 제조 이온주입 공정의 이온 임플란타 장치에서 엑스레이 발생 특성"

박동욱[1*] · 조경이[2,3] · 김소연[4] · 이승희[1] · 정은교[5]

[1]한국방송대학교 보건환경학과, [2]서울대학교 보건대학원 환경보건학과,
[3]국립암센터 암예방사업부, [4]창원파티마병원, [5]오산대학교 산업안전보건과

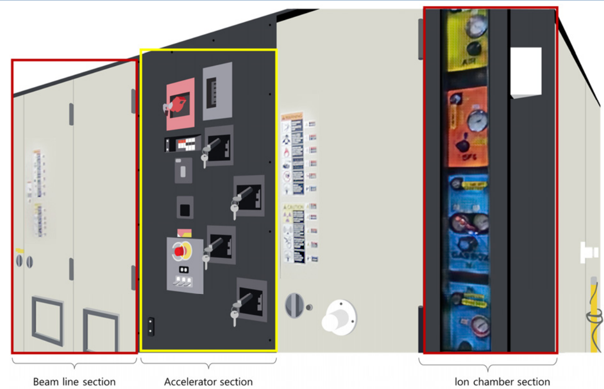
Erratum to "Characterization of X-ray Emitted in the Ion Implantation Process of Semiconductor Operations"

Dong-Uk Park[1*] · Kyung Ehi Zoh[2,3] · Soyeon Kim[4] · Seunghee Lee[1] · Eun Kyo Jeong[5]

[1]Department of Environmental Health, Korea National Open University
[2]Department of Environmental Health, Graduate School of Public Health, Seoul National University
[3]National Cancer Control Institute, National Cancer Center
[4]Changwon Fatima Hospital, Changwon, Republic of Korea
[5]Department of Industrial Safety and Health, Osan University

한국산업보건학회 편집위원회는 본 논문의 일부 내용(figure2)에 대해 저자들의 변경 신청을 접수 받았습니다. 이에 편집위원회는 변경 신청 사항을 검토하여, "정오표(Erratum)" 제시로 최종 결정하였습니다.

Erratum : 반도체 제조 이온주입 공정의 이온 임플란타 장치에서 엑스레이 발생 특성, 한국산업보건학회지, 제33권 제4호(2023) 중 그림(Figure) 2를 그림 내용을 더 분명하게 나타내 독자의 이해를 더 쉽게 하기 위해 교체합니다.

수정 전	수정 후
  Figure 2. Three points where X-ray was monitored in ion implantation process (beam line, panel behind high voltage electric system, and ion source chamber)	 Figure 2. Three points where X-ray was monitored in ion implantation process (beam line, panel behind high voltage electric system, and ion source chamber)

*Corresponding author: Dong-Uk Park, Tel: +82-2-3668-4707 , E-mail: pdw45@gmail.com
Department of Environmental Health, Korea National University, 86 Daehak-ro, Jongnogu, Seoul, 03087, Republic of Korea
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Dong-Uk Park https://orcid.org/0000-0003-3847-7392
Kyung Ehi Zoh https://orcid.org/0000-0002-2821-070X
Soyeon Kim https://orcid.org/ 0000-0001-8080-3126
Seunghee Lee https://orcid.org/0000-0003-4693-811X
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